



Wafer Handling and Photo Conference



June 25, 2019 | Dresden, Germany

Entegris Technology Day

Deutsche Werkstätten Hellerau | Dresden, Germany

25th of June, 2019

10:00	Registration & Welcome Coffee
10:30	Entegris Today
	Antoine Amade, Sr., Regional Director EMEA
10:45	Wafer & Reticle Handling - Protect from Damage and Contamination
	Decontamination Solutions to Control AMCs in FOUPs
	Paola Gonzalez-Aguirre Ph.D., Engineer II, CEA/LETI assignee
	Cross Contamination from FOUPs to Wafers: A Complex Phenomenon
	Thin Substrates Handling and Shipping
	Holger Walther, Technologist EMEA - Wafer Handling
	13 Wafer capacity FOUP for thin substrate transport
	Shipping of finished substrates in contactless HWS or FOSB
	Secure Your Reticle during Transport and Storage
	Jorgen Lundgren - Sr. Field Application Engineer
	Reticle SMIF pod overview
	Haze prevention in lithography tool (Clarilite)
	EUV 1010 update









Wafer Handling and Photo Conference



June 25, 2019 | Dresden, Germany

Entegris Technology Day

Deutsche Werkstätten Hellerau | Dresden, Germany

25th of June, 2019

12:15	Networking Lunch sponsored by Entegris
13:45	Entegris Today Antoine Amade, Sr., Regional Director EMEA
14:00	Photolithography - Control Your Process and Environment
	Leverage on Filtration to Improve Your Operating Efficiency

Leverage on Filtration to Improve Your Operating Efficiency

Laurent Stock, Technologist EMEA - Dispense & Packaging

- Contamination challenges
- Control contamination to reduce latent defects

Optimize Your Resist Delivery

Laurent Stock, Technologist EMEA - Dispense & Packaging

- Advanced two-stage technology enables separation of dispense and filtration steps
- IntelliGen® LV ensures dispense repeatability, longer filter life and a greater return on investment
- Network interface capability allows advanced process monitoring and controls

15:00 Networking Refreshment Break

15:20 Airborne Molecular Contamination Control in the Lithography Module

Mike Alexander, AMC Filtration Global Business Development

- TMS and organic AMC control strategies to address lithography scanner optics contamination and extend filter service life
- VaporSorbTM TRK filter solutions for broad spectrum AMC control in the prevention of resist defects in coat equipment
- Automated AMC Sample Collection Using the CollectTorr Device

$Transport \, \& \, Protect \, Your \, Sensitive \, Chemicals \, in \, Safe \, and \, Cost-Effective \, Liquid \, Packaging \, Solution \, Transport \, \& \, Protect \, Your \, Sensitive \, Chemicals \, in \, Safe \, and \, Cost-Effective \, Liquid \, Packaging \, Solution \, Transport \, \& \, Protect \, Your \, Sensitive \, Chemicals \, in \, Safe \, and \, Cost-Effective \, Liquid \, Packaging \, Solution \, Transport \, & \, Protect \, Your \, Sensitive \, Chemicals \, Cost-Effective \, Chemicals \, Chemi$

Laurent Stock, Technologist EMEA - Dispense & Packaging

- NowPak® bag-in-bottle technology
- New developments & roadmap
- Continuous improvement plan udpates

16:30 Wrap-up

